

**IN THE SPECIFICATION:**

Please amend the Specification as follows:

**On page 11:**

[00043] *a first support structure (a mask table) MT:* for supporting patterning devices (e.g. a mask) MA and connected to first positioning mechanism PM for accurately positioning the patterning devices with respect to item PL and measurement structure IF1;

[00044] *a second object table (substrate table or substrate holder) WT:* provided with a substrate holder for holding a substrate W (e.g. a resist-coated silicon wafer), and connected to second positioning mechanism PW for accurately positioning the substrate with respect to item PL and measurement structure IF IF2 (e.g., interferometric) to accurately indicate the position of the substrate and/or substrate table with respect to lens PL; and